

REACTIVE ION ETCHING SYSTEM

STANDARD FEATURES:

Compact Table Top Design
for Isotropic Etching of Samples
(20" x 24" Footprint)

Aluminum or Stainless Steel
Chamber with Top Opening
(Clamshell Style)

Small View Port on Chamber

Water Cooled 6" Wafer/Sample Stage
(Accommodates Up to One 6" Wafer)

Uniformity of Etching/Cleaning
(Less than 5% over a 6" Wafer)

RF Power Supply with Matching
Network

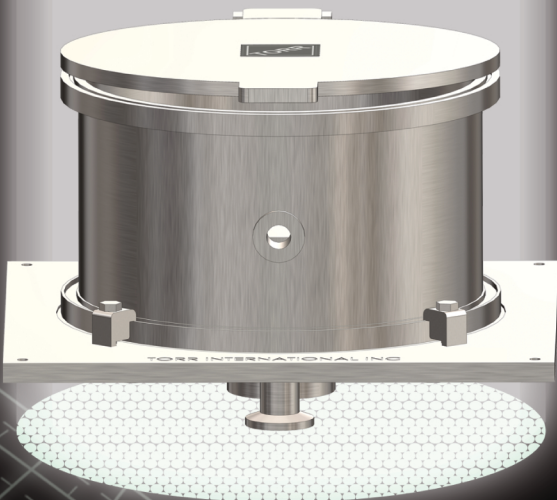
Turbo Molecular Vacuum Pumping
System with Matching Dual Stage
Rotary Vane Pump

Mass Flow Controller with Digital
Readout for Process Gas

Custom Integral Gas Shower

Vacuum Gauge with Digital
Display and Readout
(Measures to 0.1m Torr)

PLC controlled system



OPTIONAL FEATURES:

Water Chiller

Gas Scrubber

RF Power Supply with Automatic
Matching Network & Network Controller

PC Controlled System

Manifold for Multiple Mass Flow
Controllers for Various Process Gases

Additional Spare Flanges for
Future Upgrades

Corrosive Resistant Hardware

- Pumping System

- All Metal-Sealed Mass Flow Controllers

- Vacuum Gauge & Fittings

Manifold for Multiple Mass Flow
Controllers for Various Process Gases

Isolated Full Range Vacuum Gauge with
Digital Display & Readout

(for pre-process base pressure measurement)



1 Torr = 1 mm Hg

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